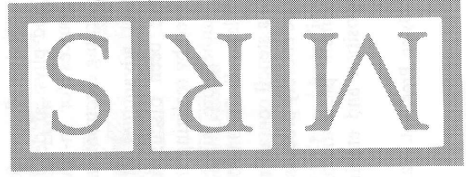


Another Step in  
Developing a Single  
Wafer Integrated  
Process: Rapid Thermal  
Low Pressure  
Metalorganic Chemical  
Vapor Deposition of  
Local Diffused  
W(Zn) Contacts

A. Katz, A. Feingold,  
El-Roy, N. Moriya,  
S.J. Pearton, A. Rusby,  
J. Kovalchick,  
C.R. Abernathy, M. Geva and  
E. Lane



PROCEEDINGS  
REPRINT

Reprinted from Materials Research Society  
Symposium Proceedings Volume 282, Chemical  
Perspectives of Microelectronic Materials III, C.R.  
Abernathy, C.W. Bates, Jr., D.A. Bohling and  
W.S. Hobson, editors.